

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the application of:

Srivatsa KUNDALGURKI

Serial No.:

10/734,593

Filing Date:

December 15, 2003

For:

METHOD FOR REMOVING A RESIST MASK WITH HIGH SELECTIVITY TO A CARBON HARD MARK USED FOR

SEMICONDUCTOR STRUCTURING

Examiner: E. T. PERT

Group Art Unit: 2829

Confirmation No. 1431

## **DECLARATION UNDER 37 C.F.R. 1.131**

- I, Srivatsa KUNDALGURKI, hereby declare that:
- 1. I am the sole inventor, who filed the above-identified application on December 15, 2003.
- 2. I completed my invention, having made thereof and disclosed the same to others, in this country prior to the November 19, 2003 filing date of the Ohuchi et al. reference (US 2004/0144491 A1). Please be advised that the invention report for this invention was made on July 16, 2003.
- 3. I do not know and do not believe that the invention has been in public use or on sale in this country, or patented or described in a printed publication in this or any other foreign country for more than one year prior to our application, and I have never abandoned my invention.
- 4. The undersigned declares further that all statements made herein of his own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section

1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

Date: January 28, 2005

Srivatsa KUNDALGURKI